



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor application of:  
Thomas A. Figura, Kevin Donohoe, & Thomas Dunbar

Serial No.: 09/471,460

Filed: December 22, 1999

Title: USE OF A PLASMA SOURCE TO FORM A LAYER  
DURING THE FORMATION OF A SEMICONDUCTOR DEVICE

§  
§ Group Art Unit: 2825  
§  
§ Application Examiner: Calvin Lee  
§  
§ Atty. Docket: 94-0280.03  
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Reply  
Actual  
3/22/04

RESPONSE TO THE OFFICE ACTION DATED MARCH 28, 2003

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Certificate of Mailing	
I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on:	
Date <u>6/30/03</u>	<u>Susan Jerome</u> Signature

Dear Sir:

Applicants submit this Response to the Office Action dated March 28, 2003.

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02 FC:1201 84.00 DA  
03 FC:1202 18.00 DA

Remarks

Claims 45-46 are pending.

Claims 45-46 are rejected.

Applicants request reconsideration of claims 45-46.

I. Rejection of claims under 35 U.S.C. §112

The Examiner rejected claims 45-46 based on 35 U.S.C. §112, ¶2, concluding that they are indefinite based on the term "generally simultaneously." That term is used in those claims to relate the act of performing a deposition of a material and the act of etching that material. The Examiner argued that the term is not used with respect to the

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